EFS-Web Receipt date: 08/21/2006



PATENT Attorney Docket No. ASC-049C1

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT(S):

Fitzgerald

CONFIRMATION NO.

SERIAL NO.:

10/774,890

**GROUP NO.:** 

2818

FILING DATE:

February 9, 2004

EXAMINER:

Tran, Mai Huong C.

TITLE:

RELAXED SIGE PLATFORM FOR HIGH SPEED CMOS

ELECTRONICS AND HIGH SPEED ANALOG CIRCUITS

# CERTIFICATE OF FIRST CLASS MAILING UNDER 37 C.F.R. 1.8

I hereby certify that this correspondence, and any document(s) referred to as enclosed herein, is/are being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on this 17<sup>th</sup> day of August, 2006.

Linda M. Penta

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

### Submitted herewith is/are:

- 1. Transmittal Form (1 page);
- 2. Second Supplemental information Disclosure Statement (2 pgs.);
- 3. Form USPTO-1449 (1 pg.);
- 4. Copies of cited references C166-C173); and
- 5. Return receipt postcard.

			Application Serial Number		10/774,890		
			Filing Date		Febru	February 9, 2004	
		First Named	t Named Inventor Fi		Fitzgerald		
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6	PE \	Examiner N	ame	Fitzge	rald		
	FORM		Attorney Do	ocket No.	ASC-	049C1	
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TO TO	MARMAN	ENG	CLOSURES (c	CLOSURES (check all that apply)			
☐ Fee	: Transmittal Form			e to File Missing		Notice of Appeal to Board	
	Check Attached		Parts of Applic			of Patent Appeals and Interferences	
	Copy of Fee Transmittal Form		Formal Drawin	ng(s)		Appeal Brief (in triplicate)	
Image: section of the content of the	Amendment/Response		Request For Continued Examination (RCE)			Status Inquiry	
	☐ Preliminary ☐ After Final		Transmittal			Return Receipt Postcard	
	☐ Affidavits/declaration(s) ☐ Letter to Official ☐ Draftsperson		Power of Attor (Revocation of	rney f Prior Powers)	$\boxtimes$	Certificate of First Class Mailing under 37 C.F.R. 1.8	
	including Drawings [Total Sheets]		Terminal Disc	laimer		Certificate of Facsimile Transmission under 37 C.F.R. 1.8	
	Petition for Extension of Time			aration and Power r Utility or Design tion		Additional Enclosure(s) (please identify below)	
⊠ .	Supplemental Information Disclosure Statement		Small Entity Statement  CD(s) for large table or computer program				
	Form PTO-1449 Copies of SIDS Citations (C166-173)						
	Document(s)  Sequence Listing submission Paper Copy/CD			Amendment After Allowance			
			Request for Certificate of Correction Certificate of Correction (in duplicate)				
CORRI	ESPONDENCE ADDRESS		SIGNATURE BLOCK				
Direct all correspondence to:  Patent Administration Goodwin Proct Exchange Place Boston, MA 0 Tel. No.: (617) Fax No.: (617) Customer No. (6			Date: August 17, 2006 Reg. No. 44,381 Tel. No.: (617) 570-1806 Fax No.: (617) 523-1231  Date: August 17, 2006 Natasha C. Attorney for Goodwin Fexchange		Natasha C. Us Attorney for the Applicant Goodwin Procter LLP Exchange Place Boston, MA 02109		

EFS-Web Receipt date: 08/21/2006 10774890 - GAU: 2818



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TRAN, MAI HUONG C.

TITLE:

RELAXED SIGE PLATFORM FOR HIGH SPEED CMOS

**ELECTRONICS AND HIGH SPEED ANALOG CIRCUITS** 

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

# SECOND SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with the provisions of 37 C.F.R. 1.97 and 1.98, Applicants hereby make of record the publications listed on the accompanying Form PTO-1449, and other information contained herein, for consideration by the Examiner in connection with the examination of the above-identified patent application. In accordance with 37 C.F.R. 1.98(a)(2), only copies of the non-patent publications are enclosed.

### **REMARKS**

In accordance with the provisions of 37 C.F.R. 1.97, this statement is being filed (CHECK ONE):

(1)	within three (3) months of the <b>filing date</b> of a national application other than a continued prosecution application under 37 C.F.R. 1.53(d), or within three (3) months of the <b>date of entry of the national stage</b> as set forth in 37 C.F.R. 1.491 in an international application, or before the mailing of the <b>first Office action</b> on the merits, or before the mailing of a <b>first Office action</b> after the filing of a request for continued examination under 37 C.F.R. 1.114; or
(2)	after the period defined in (1) but before the mailing date of a final action or a notice of allowance under 37 C.F.R. 1.311, and
	the requisite Statement is below, OR
	the requisite fee under 37 C.F.R. 1.17(p), namely \$180.00, is included herein, or

Supplemental Information Disclosure Statement Serial No. 10/774,890

Page 2 of 2

(3)	after the mailing date of a final action or notice of allowance but before the payment of the issue fee, AND					
	the requisite Statement is below, AND					
	the requisite petition fee under 37 C.F.R. 1.17(p), namely \$180.00 is included herein.					

It is respectfully requested that each of the publications listed on the attached Form PTO-1449, and other information contained herein, be made of record in this application.

#### **STATEMENT**

As required under 37 C.F.R. 1.97(e), Applicant(s), through the undersigned, hereby state either that [check the appropriate space only if either (2) or (3) is checked on the previous page <u>and</u> the Statement is required]:

- 1. Each item of information contained in the Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application **not more than three months** prior to the filing of the Information Disclosure Statement; or
- No item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing this Statement after making reasonable inquiry, no item of information contained in the Information Disclosure Statement was known to any individual designated in 37 C.F.R.
   1.56(c) more than three months prior to the filing of the Information Disclosure Statement.

Respectfully submitted,

Date: August 17, 2006 Reg. No. 44,381

Tel. No.: (617) 570-1806 Fax No.: (617) 523-1231 Natasha C. Us

Attorney for Applicant Goodwin Procter LLP Exchange Place

Boston, Massachusetts 02109

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Customer No. 051414

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Sheet 1 of 1

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Fitzgerald

FILING DATE: February 9, 2004

EXAMINER: Tran. Mai Huong C.

					EXAMINER:	Tran,	Mai Huon	g C.	
					GROUP:	2818			
				U.S. PAT	ENT DOCUMENT	S			
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
		,							
			OTHE	R ART, JO	OURNAL ARTICLE	ES, ETC.			
EXAM. OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Palinit.						ges, Place o	f Publicatio	on)	
	C166 Kubota M., et al. "New SOI CMOS Process with Selective Oxidation," IEEE IEDM TECH. DIG., pp. 8 816, (1986).							OM TECH. DIG., pp. 814-	
	C167	Ming et al., "Interfacial roughness scaling and strain in lattice mismatched Si <sub>0.4</sub> Ge <sub>0.6</sub> thin films on Si" Applied Physics Letters, Vol. 67, No. 5, July 31, 1995, pp. 629-631.							
	C168	Ming et al., "Microscopic structure of interfaces in Si <sub>1-x</sub> Ge <sub>x</sub> /Si heterostructures and superlattices studied by x-ray scattering and fluorescence yield," Physical Review B, Vol. 47, No. 24, pp. 373-81, June 15, 1993.							
	C169	Nishi et al. "Handbook of Semiconductor Manufacturing Technology," Marcel Dekker AG, New York, NY, 2000, pp. 1-22							
	C170	O'Neill, et al., "Deep Submicron CMOS Based on Silicon Germanium Technology," <i>Fellow</i> , IEEE Transactions on Electron Devices, Vol. 43, No. 6, June 1996 pp. 911-918.							
	C171 Sugii, et al., "Role of Si <sub>1-x</sub> Ge <sub>x</sub> buffer layer on mobility enhancement in a strained-Si channel me semiconductor field-effect transistor," Central Research Laboratory, Hitachi Ltd. 1-280 Higashi-Koigakuboj, Kokubunji-shi, Tokyo 185-8601 Japan, pp. 2948-2950. unknown date						1-280 Higashi-		
	C172	Vossen et al. "Thin Film Processes II" Academic Press Inc., San Diego, CA, 1991, pp. 370-442.							
	C173	Wolfe et al. "Silicon Processing for the VLSI Era, Volume 1; Process Technology," Lattice Press 1986, pp. 124-160.							
EXAMINER /Dung A. Le/ (07/14/2008)					DATE CONSIDERED				

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /Die/ (07/14/2008)

DATE CONSIDERED

LIBC/2796158.1